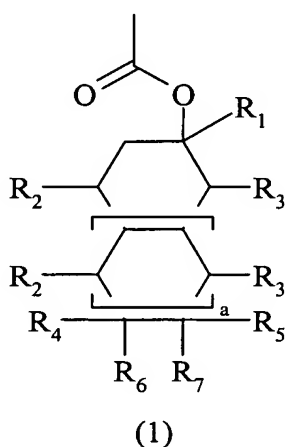


This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) A polymer containing a group of the following general formula (1) and having a weight average molecular weight of 1,000 to 500,000,



wherein ~~R¹ to R³ each are~~ is hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, and ~~R² and R³ may~~ bond together to form a ring ~~and in that event, such that~~ each is an alkylene group of 1 to 20 carbon atoms which ~~may contain a~~ optionally contains an oxygen, sulfur or nitrogen hetero atom ~~such as oxygen, sulfur or nitrogen,~~

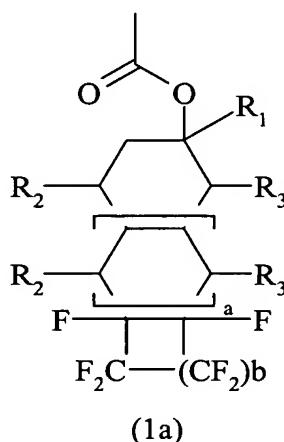
R⁴ and R⁵ each are hydrogen or fluorine,

R⁶ and R⁷ each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R⁶ and R⁷ contains at least one fluorine atom, or alternatively R⁶ and R⁷ ~~may~~ bond together to form a ring and in that event,

each is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, and

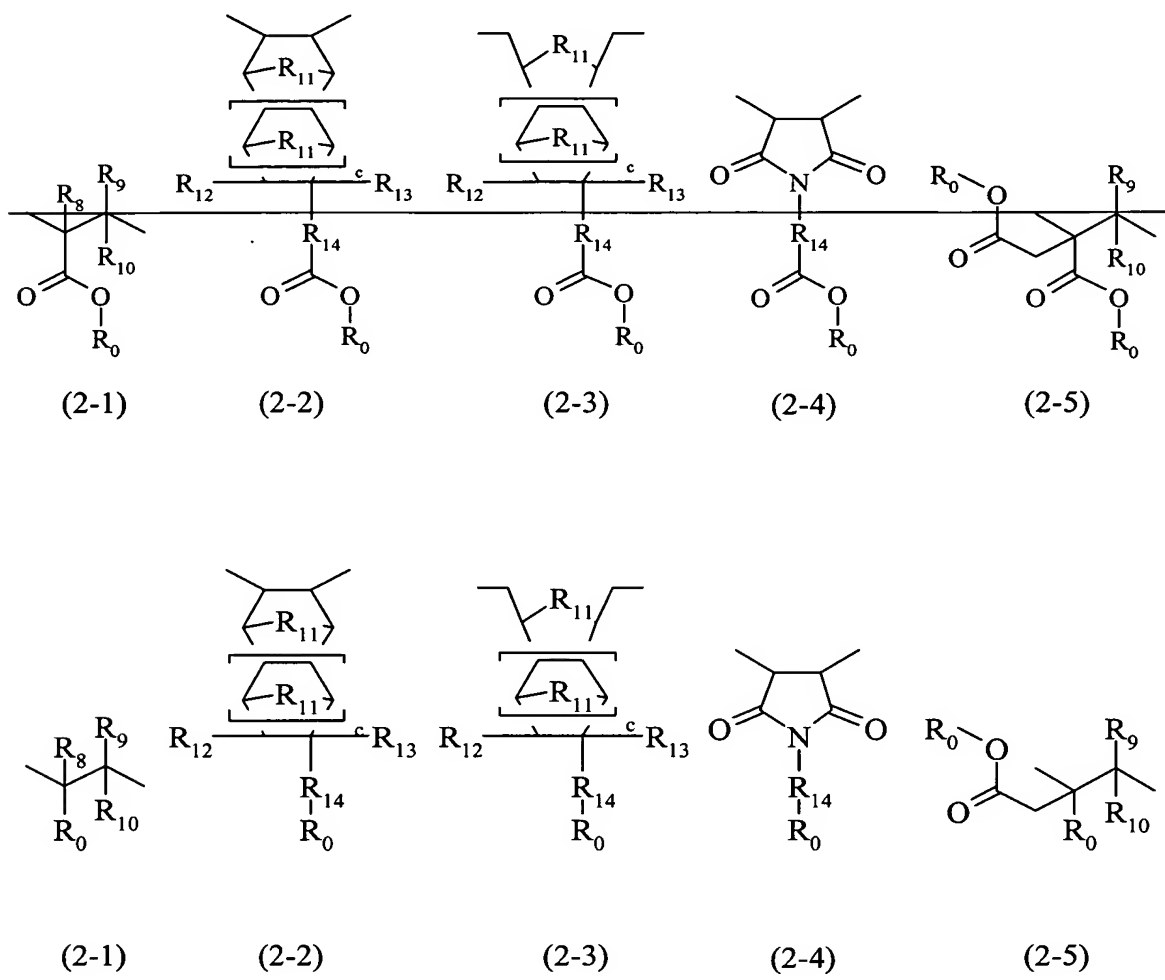
"a" is 0 or 1.

2. (Currently Amended) The A polymer of claim 1 containing a group of the following ~~general~~ formula (1a) and having a weight average molecular weight of 1,000 to 500,000:



wherein R^1 to R^3 each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, or alternatively R^2 and R^3 ~~may~~ bond together to form a ring and in that event, each is an alkylene group of 1 to 20 carbon atoms which ~~may~~ contain optionally contains a hetero atom such as oxygen, sulfur or nitrogen, "a" is 0 or 1, and "b" is an integer of 1 to 4.

3. (Currently Amended) The polymer of claim 1 having a partial structure of any one of the following ~~general~~ formulae (2-1) to (2-5):



wherein R^0 is a group of formula (1) in claim 1 or a group of formula (1a) in claim 2,

R^8 to R^{10} each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms,

R^{11} is a methylene group, oxygen atom or sulfur atom,

R^{12} and R^{13} each are hydrogen, methyl or $\text{CH}_2\text{CO}_2R^{15}$,

R^{14} is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms,

R¹⁵ is a straight, branched or cyclic alkyl or substituted alkyl group of 1 to 20 carbon atoms, and

“c” is 0 or 1.

4. **(Original)** A resist composition comprising the polymer of claim 1.

5. **(Previously presented)** A chemically amplified, positive resist composition comprising
 - (A) the polymer of claim 1,
 - (B) an organic solvent, and
 - (C) a photoacid generator.

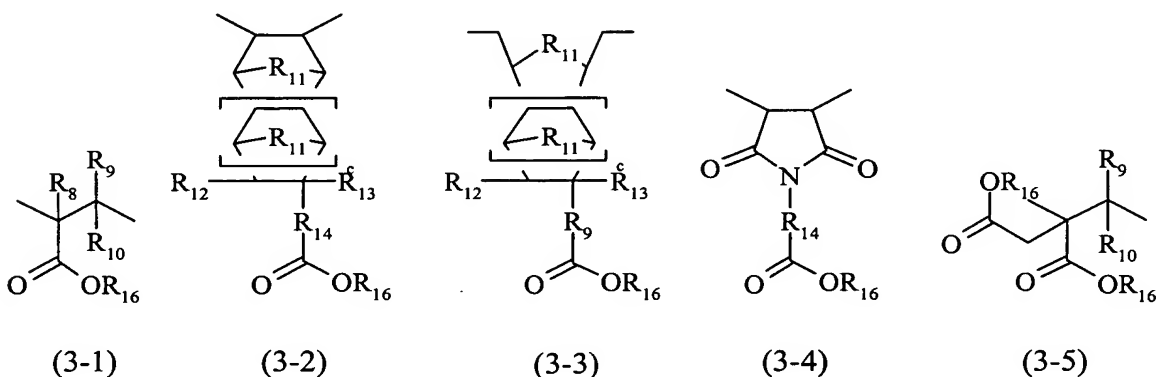
6. **(Original)** The resist composition of claim 5 further comprising (D) a basic compound.

7. **(Original)** The resist composition of claim 5 further comprising (E) a dissolution inhibitor.

8. **(Original)** A process for forming a resist pattern comprising the steps of:
 - applying the resist composition of claim 4 onto a substrate to form a coating,
 - heat treating the coating and then exposing it to high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photo mask, and
 - optionally heat treating the exposed coating and developing it with a developer.

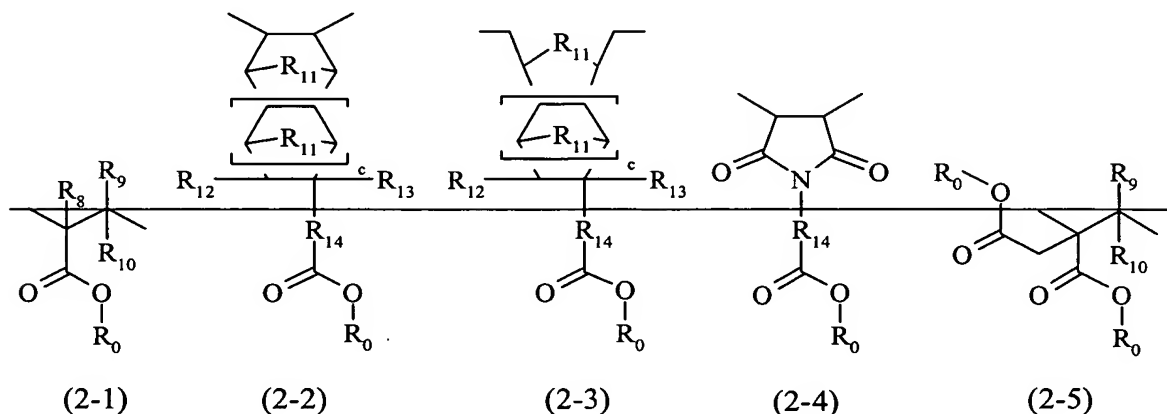
9. (Original) The pattern forming process of claim 8 wherein the high-energy radiation is an F₂ laser beam, Ar₂ laser beam or soft x-ray.

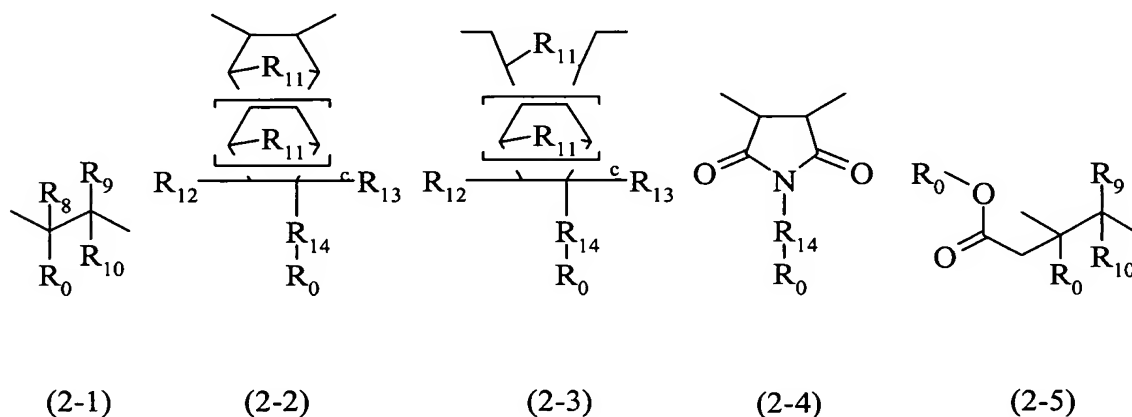
10. (New) The polymer of claim 3 which additionally comprises recurring units of one of formulae (3-1) to (3-5):



wherein, R⁸ to R¹⁵ and c are as defined above, and R¹⁶ is an acid labile group.

11. (New) The polymer of claim 2 having a partial structure of any one of the following formulae (2-1) to (2-5):





wherein R^0 is a group of formula (1a) in claim 2,

R^8 to R^{10} each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms,

R^{11} is a methylene group, oxygen atom or sulfur atom,

R^{12} and R^{13} each are hydrogen, methyl or $\text{CH}_2\text{CO}_2R^{15}$,

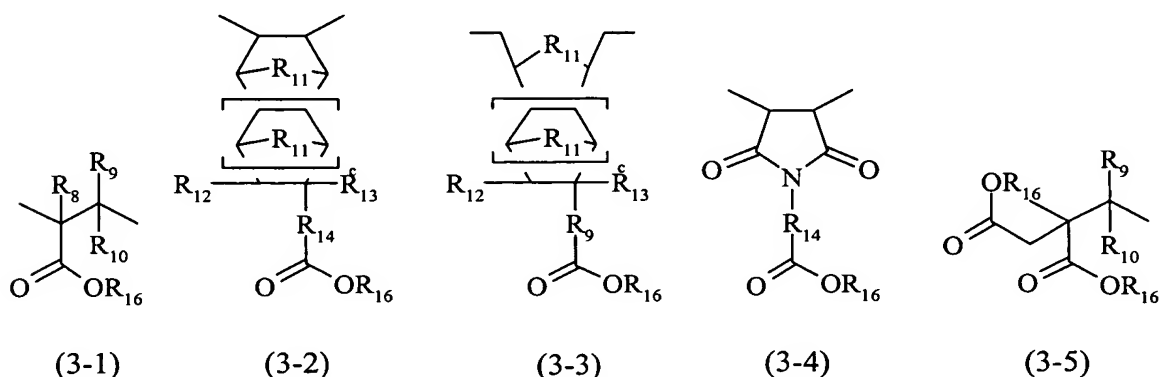
R^{14} is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms,

R^{15} is a straight, branched or cyclic alkyl or substituted alkyl group of 1 to 20 carbon atoms, and

“c” is 0 or 1.

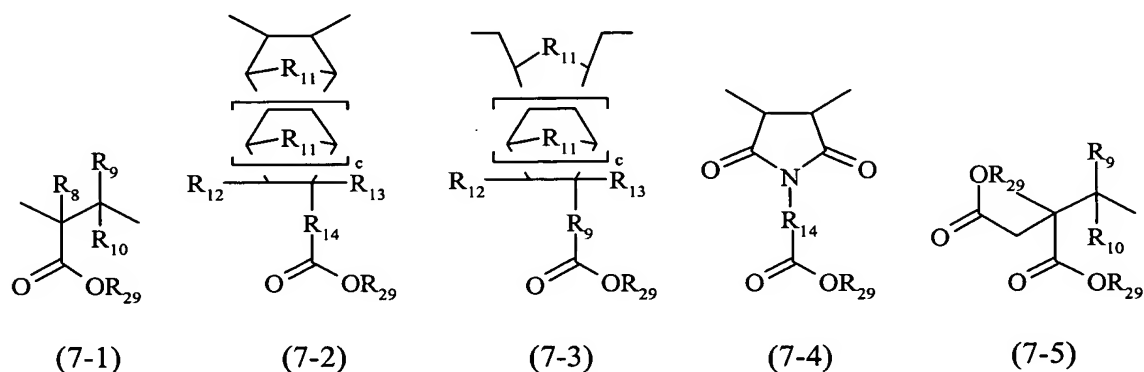
12. (New) A resist composition comprising the polymer of claim 2.

13. (New) A chemically amplified, positive resist composition comprising
 - (A) the polymer of claim 2,
 - (B) an organic solvent, and
 - (C) a photoacid generator.
14. (New) The resist composition of claim 13 further comprising (D) a basic compound.
15. (New) The resist composition of claim 13 further comprising (E) a dissolution inhibitor.
16. (New) A process for forming a resist pattern comprising the steps of:
 - applying the resist composition of claim 12 onto a substrate to form a coating,
 - heat treating the coating and then exposing it to high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photo mask, and
 - optionally heat treating the exposed coating and developing it with a developer.
17. (New) The pattern forming process of claim 16 wherein the high-energy radiation is an F₂ laser beam, Ar₂ laser beam or soft x-ray.
18. (New) The polymer of claim 11 which additionally comprises one or more recurring units of one of formulae (3-1) to (3-5):



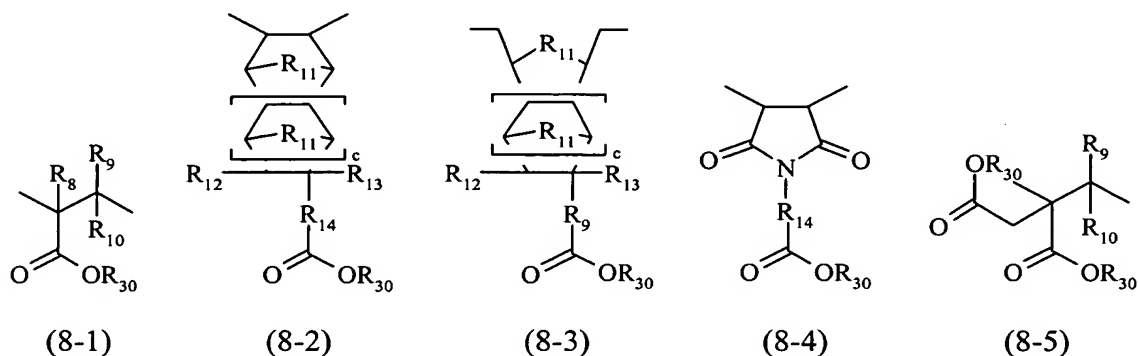
wherein, R^8 to R^{15} and c are as defined above, and R^{16} is an acid labile group.

19. (New) The polymer of claim 3 which additional comprises one or more recurring units of one of the formulae (7-1) to (7-5)



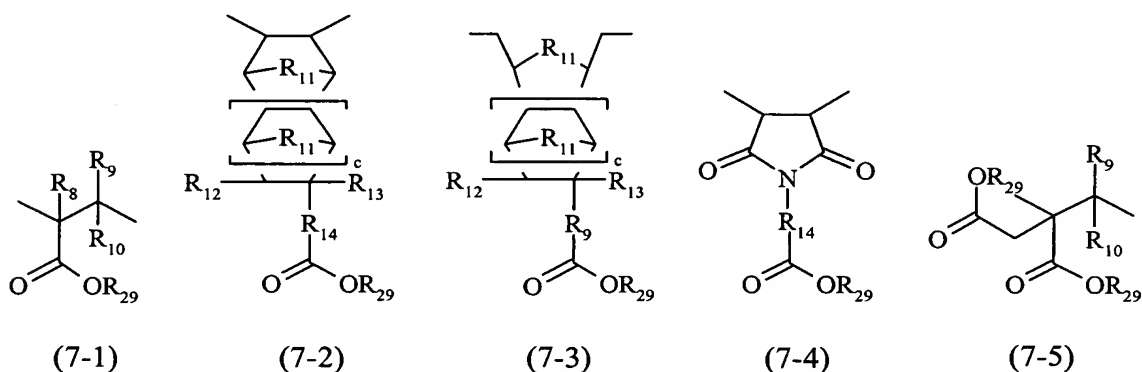
wherein, R^8 to R^{15} and c are as defined above, and R^{29} is a fluorinated alkyl group having 2 to 20 carbon atoms.

20. (New) The polymer of claim 3 which additional comprises one or more recurring units of one of the formulae (8-1) to (8-5):



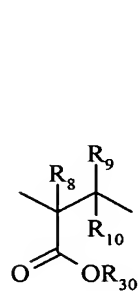
wherein, R^8 to R^{15} and c are as defined above, and R^{30} is hydrogen or an adhesive group.

21. (New) The polymer of claim 11 which additional comprises one or more recurring units of one of the formulae (7-1) to (7-5)

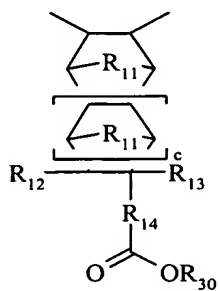


wherein, R^8 to R^{15} and c are as defined above, and R^{29} is a fluorinated alkyl group having 2 to 20 carbon atoms.

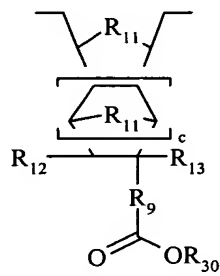
22. (New) The polymer of claim 11 which additional comprises one or more recurring units of one of the formulae (8-1) to (8-5):



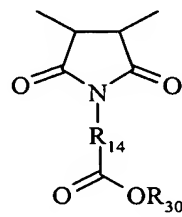
(8-1)



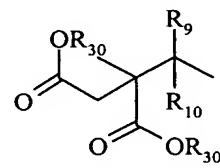
(8-2)



(8-3)



(8-4)



(8-5)

wherein, R^8 to R^{15} and c are as defined above, and R^{30} is hydrogen or an adhesive group.